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L15 ANSWER 5 OF 12 HCAPLUS COPYRIGHT 2003 ACS on STN
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Remote plasma cleaning method for semiconductor processing chambers ΤI

Rajagopalan, Ravi; Liu, Patricia M.; Narwankar, Pravin K.; Tran, Huyen; IN Krishnaraj, Padmanabhan; Ablao, Alan; Casper, Tim

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Patent

DT

LΑ English ICM H05H001-00 IC

NCL 216067000

76-11 (Electric Phenomena) CC

Section cross-reference(s): 47, 75

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	PATENT NO.	KIND DATE	APPLICATION NO.	DATE
ΡI	US 6274058	B1 20010814	US 1999-347236	19990702
	US 6125859	A 20001003	US 1997-893922	19970711
	TW 385494	B 20000321	TW 1998-87111364	19980713
	EP 1065295	A1 20010103	EP 2000-113942	20000630
		CH, DE, DK, ES,	FR, GB, GR, IT, LI, LU,	NL, SE, MC, PT,
		LT, LV, FI, RO		
	JP 2001085418	A2 20010330	JP 2000-201117	20000703
PRAI	US 1997-893922	A2 19970711		
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	US 1999-347236	A 19990702		_

A processing chamber cleaning method is described which uses microwave AB energy to remotely generate a reactive species to be used alone or in combination with an inert gas to remove deposits from a processing chamber. The reactive species can remove deposits from a 1st processing region at a 1st pressure and then remove deposits from a 2nd processing region at a 2nd pressure. Also described is a cleaning process using remotely generated reactive species in a single processing region at 2 different pressures. Addnl., different ratios of reactive gas and inert gas may be used to improve the uniformity of the cleaning process, increase the cleaning rate, reduce recombination of reactive species and increase the residence time of reactive species provided to the processing

RL: PEP (Physical, engineering or chemical process); PROC (Process) (remote plasma cleaning method for semiconductor processing chambers)

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Tantalum, [2-(dimethylamino-.kappa.N)ethanolato-.kappa.0]tetraethoxy-, CN (OC-6-23) - (9CI) (CA INDEX NAME)